

ABSTRACT
SUBSTRATE PROCESSING APPARATUS

Provided is a substrate processing apparatus that includes: a rotary joint including a rotary unit that rotates together with the rotation of the head unit, a fixing unit that is provided around the rotary unit, and a sealing unit that seals a gap between the rotary unit and the fixing unit; and an outlet pipe through which the quenching water is discharged. A first flow passage through which a gas passes and a second flow passage through which the quenching water passes are formed in the rotary joint, and the second flow passage is isolated from the first flow passage by the sealing unit. One end of the outlet pipe communicates with an outlet port of the second flow passage of the rotary joint, and the other end of the outlet pipe is opened to atmosphere at a position lower than the outlet port of the second flow passage.

Figure 4